Corial 210IL - 200 mm INDUCTIVELY COUPLED SYSTEM

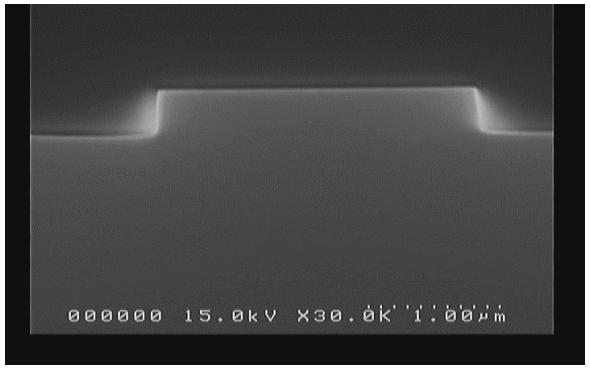
Specifications

Wafer size	4" 6" 8"
MFC gas lines	SF6 C4F8 CHF3 Cl2 Ar O2
Process temperature	-30ºC 150ºC
Vaccum load lock	Manual loading
EPD camera system	laser interferometry 670nm
3 liners configuration	Si,SiO2,SiN/metals/III-V materials
ICP/RF generator	2000W/1000W

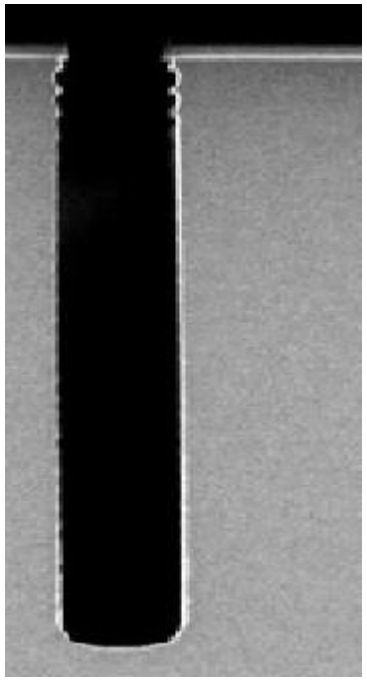
DESCRIPTION:

The CORIAL etching systems are designed for high resolution etching of any etchable material (material that can be combined with F, Cl, C and H atoms to form volatiles compounds). The anisotropy, selectivity and uniformity required for manufacturing of integrated circuits and LEDs, OLEDS devices with critical micronic and submicronic dimensions on materials as Si, SiO2, Si3N4, polymers, III-V and II-VI compounds, sapphire and metals.

EXAMPLES:



220nm silicon waveguide on SOI wafer



Deep Silicon trench
BOSCH process